

Amendments to the Claims:

The following listing of claims replaces all prior versions and listings of claims, in the application.

Listing of Claims

1. (Previously Presented) A continuous-operation scrubber system to remove contaminants in a gas in a semiconductor processing tool comprising:
  - a semiconductor processing tool;
  - a pair of channels connected in parallel to a supply line of the semiconductor processing tool;
  - a scrubber coupled with each channel that removes a gas contaminant from each channel such that a scrubbed gas is delivered through the supply line to the semiconductor processing tool; and
  - a purge system coupled with each scrubber for purging the removed gas contaminant from each scrubber.
2. (Previously Presented) The continuous-operation scrubber system of Claim 1 further comprising a control system for directing a flow of gas through the channels.
3. (Previously Presented) A method for continuously scrubbing a gas in a semiconductor processing tool comprising the steps of:
  - delivering a gas to a scrubber system for a semiconductor processing tool including a first scrubber and a second scrubber connected in parallel;
  - directing the gas through the first scrubber;
  - purging the first scrubber while directing the gas through the second scrubber; and
  - purging the second scrubber while directing the gas through the first scrubber, the scrubbed gas from the first scrubber and the second scrubber being delivered to a semiconductor processing tool.

4. (Previously Presented) The method of Claim 3 wherein flow of the gas alternates between passing through the first scrubber and passing through the second scrubber.
5. (Previously Presented) The system of claim 1 wherein the purge system is coupled to at least one of the scrubbers for purging reversibly-bound basic nitrogen compounds from the scrubber.
6. (Previously Presented) The system of claim 1 wherein at least one of the scrubbers includes a cation exchange medium.
7. (Previously Presented) The system of claim 1 further comprising a converter and a flow controller that selectively controls which of the scrubbing channels the gas can flow through to the converter.
8. (Previously Presented) The system of claim 7 further comprising a detector wherein the flow controller is governed by a control system that is programmed to transfer the flow of a reference gas reaching the detector from a scrubbing channel with a contaminated scrubber to a scrubbing channel with a purged scrubber and to then direct a purge gas through the contaminated scrubber.
9. (Previously Presented) The system of claim 8 wherein the control system is programmed to transfer the flow of the reference gas away from one of the scrubbing channels and to purge the scrubber of that scrubbing channel before a weak-base nitrogen compound can penetrate through the scrubber.
10. (Currently Amended) The system of claim 9 further comprising a primary channel wherein the control system is programmed to alternately transfer the flow of a gas between the primary channel, ~~where the gas comprises a target gas,~~ and one of the scrubbing channels, ~~where the gas comprises a reference gas.~~

11. (Previously Presented) The system of claim 1 further comprising a detector and a pressure reducer located between the detector and the scrubbers.
12. (Previously Presented) The method of claim 3 further comprising the steps of:  
passing a first reference gas through the first scrubber to remove basic nitrogen compounds from a first reference gas; and  
passing a second reference gas through a second scrubber to remove basic nitrogen compounds from the second reference gas.
13. (Previously Presented) The method of claim 3 further comprising purging the first scrubber to remove reversibly-bound basic nitrogen compounds while passing a second reference gas through the second scrubber.
14. (Previously Presented) The method of claim 3 further comprising passing a first reference gas and a second reference gas through a converter which converts gaseous nitrogen compounds in first and second reference gases into an indicator gas after the first reference gas passes through the first scrubber and the second reference gas passes through the second scrubber.
15. (Previously Presented) The method of claim 14 further comprising directing the first and second reference gases to a detector which detects a concentration of the indicator gas in the first or second reference gas after the said reference gas is passed through the converter.
16. (Previously Presented) The method of claim 15 further comprising passing a target gas through the converter which converts gaseous nitrogen compounds in the target gas into the indicator gas; and  
passing the target gas through the detector which detects the concentration of the indicator gas in the target gas after the target gas passes through the converter.

17. (Previously Presented) The method of claim 16 further comprising determining a total basic-nitrogen-compound contamination concentration by comparing a detected concentration of the indicator gas in the target gas with a detected concentration of the indicator gas in the reference gas.
18. (Previously Presented) The method of claim 3 further comprising alternately detecting a concentration of an indicator gas in a reference gas flowing through the first scrubber and a concentration of the indicator gas in a reference gas flowing through the second scrubber.
19. (Previously Presented) The method of claim 3 further comprising the step of alternately purging the first and second scrubbers while maintaining flow of the gas to a converter and to a detector.
20. (Previously Presented) The method of claim 3 further comprising providing a detector and a processor connected to the detector.